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areas 18 and transport system 22. In addition, wafers 16 in carriers 18 are shown. As shown in FIG. 9, the metrology station is apart from the process station and coupled to the process station.--

IN THE CLAIMS:

Cancel claims 1, 2, 4 to 7, 9, 10 and 21. Add new claims 22 and 23 as follows.

Attachment A provides a marked up version of the claim showing the changes made.

B2

3. (Amended) A semiconductor processing device comprising:
a wafer process station; and
a metrology station apart from but coupled to the process station wherein the metrology station comprises:
new matter
a light source defined by at least one lamp, said light source emitting a range of wavelengths, said range of wavelengths including visible and ultraviolet light;
optics directing light from the light source to the wafer to illuminate a region of the surface thereof and for collecting light reflected from the surface;
a spectrograph for monitoring the spectral content of the collected reflected light; and
a transport system for moving wafers between the process station and the metrology station.

B3

--22. (New) A device as recited in claim 3, wherein the optics includes a single objective lens assembly and wherein the light from the light source, including wavelengths in both the visible and ultraviolet range are focused and collected by said single objective lens.

23. (New) A device as recited in claim 22, wherein said objective lens assembly is movable and can be scanned with respect to the wafer surface.--